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DATE MAILED: 03/25/2005

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/805,992	03/22/2004	Yorito Ota	10873.0884USD1	1475
23552 75	590 03/25/2005		EXAM	INER
MERCHANT & GOULD PC			MULPURI, SAVITRI	
P.O. BOX 2903	3			
	IS, MN 55402-0903		ART UNIT	PAPER NUMBER
	•		2812	

Please find below and/or attached an Office communication concerning this application or proceeding.

			WX 配	
	Application No.	Applicant(s)		
	10/805,992	OTA, YORITO		
Office Action Summary	Examiner	Art Unit		
	Savitri Mulpuri	2812		
The MAILING DATE of this communication Period for Reply	appears on the cover sheet	vith the correspondence addres	ss	
A SHORTENED STATUTORY PERIOD FOR RE THE MAILING DATE OF THIS COMMUNICATIO - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a - If NO period for reply is specified above, the maximum statutory per - Failure to reply within the set or extended period for reply will, by state of the period for reply will be period for reply wil	N. R 1.136(a). In no event, however, may reply within the statutory minimum of the right will apply and will expire SIX (6) MG atute, cause the application to become	a reply be timely filed nirty (30) days will be considered timely. DNTHS from the mailing date of this common ABANDONED (35 U.S.C. § 133).	unication.	
Status				
1)⊠ Responsive to communication(s) filed on 3/2 2a)□ This action is FINAL. 2b)⊠ T 3)□ Since this application is in condition for allo closed in accordance with the practice under	This action is non-final. wance except for formal ma	•	erits is	
Disposition of Claims				
4) Claim(s) 9-16 is/are pending in the applicate 4a) Of the above claim(s) is/are without 5) Claim(s) is/are allowed. 6) Claim(s) 9-14 is/are rejected. 7) Claim(s) 15-16 is/are objected to. 8) Claim(s) are subject to restriction and	drawn from consideration.		,	
Application Papers				
9) The specification is objected to by the Exam 10) The drawing(s) filed on is/are: a) Applicant may not request that any objection to Replacement drawing sheet(s) including the cor 11) The oath or declaration is objected to by the	accepted or b) objected t the drawing(s) be held in abey rection is required if the drawir	ance. See 37 CFR 1.85(a). ng(s) is objected to. See 37 CFR 1		
Priority under 35 U.S.C. § 119				
12) ☑ Acknowledgment is made of a claim for fore a) ☑ All b) ☐ Some * c) ☑ None of: 1. ☐ Certified copies of the priority docum 2. ☑ Certified copies of the priority docum 3. ☐ Copies of the certified copies of the papplication from the International But * See the attached detailed Office action for a	nents have been received. The sents have been received in priority documents have been reau (PCT Rule 17.2(a)).	Application No. <u>10/079,951</u> . en received in this National Sta	age	
Attachment(s)				
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB Paper No(s)/Mail Date <u>3/22/2004</u>. 	Paper N	v Summary (PTO-413) o(s)/Mail Date f Informal Patent Application (PTO-15 	i2)	

DETAILED ACTION

This action is in response to the applicant's communication, IDS, filed on 3/22/2004.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 9-14 are rejected under 35 U.S.C. 102(e) as being anticipated by Chu et al (US 6,350,993).

Chu et al discloses a method of producing a semiconductor device, comprising: forming a semiconductor member including a SiC member and a SiGe member, wherein SiGe layer is formed over SiC substrate by crystal growth (see col. 5, lines 17-24). With respect to claims 11-13, Chu et al teaches growing Si layer as spacer layer over SiC and SiGe layer over Si I spacer layer by crystal growth (see fig. 11).

With respect to claim 12, Chu et al further teach producing semiconductor device by forming semiconductor member by crystal growth includes forming a semiconductor member with continuously variable mole fraction from SiC to Si spacer layer and from Si spacer layer to SiGe layer over SiC member (see whole structure in fig.11 for SiC-Si-

SiGe layers). Chu et al teaches ohmic contacts "113, 114" in SiGe portion of the structure. With respect to claim 14, Chu et al teaches CMOS, wherein CMOS device inherently includes both P-MOSFET and N-MOSFET devices, which requires member is formed on both n-type and p-type regions.

Claims 15-16 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Prior art teach growing SiGe layers. Mizushima et al (US 2004/0041179) teaches growing ohmic electrode on portion of SiGe layer "18" or SiC layer "28", which are formed on Si substrate (see 2B and 10).

Allowable Subject Matter

The following is an examiner's statement of reasons for allowance: Prior art neither teach nor suggest producing semiconductor device by forming gate electrode on SiC, while forming ohmic electrodes on SiGe.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Savitri Mulpuri whose telephone number is 571-272-1677. The examiner can normally be reached on Mon-Fri from 8 a.m to 4.30 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt, can be reached on 571-272-1873. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Savitri Mulpuri Primary Examiner Art Unit 2812